

ABSTRACT OF THE DISCLOSURE

An abrasive slurry that is capable of being used in a chemical mechanical polishing operation includes a plurality of abrasive particles, a matrix capable of carrying the plurality
 5 of abrasive particles, and a gettering agent. The gettering agent has an affinity for a material removed during the chemical mechanical polishing operation. A rinsing fluid that is capable of being used in a post-chemical mechanical polishing rinsing cycle. The rinsing fluid includes a gettering agent having an affinity for a residue material resulting from the chemical mechanical polishing operation.